Analysis and Design of Elementary MOS Amplifier Stages Boris Murmann

Table 4-1

unprotect('γ'):

Parameter	n-channel MOSFET	p-channel MOSFET
Threshold voltage (at V _{BS} =0)	$V_{T0n} := 0.5 [\![V]\!] :$	$V_{T0p} := -0.5 [\![V]\!] :$
Transconductance parameter	$\mu nC_{ox} := 50 \frac{\llbracket uA \rrbracket}{\llbracket V \rrbracket^2} :$	$\mu p C_{ox} := 25 \frac{\llbracket uA \rrbracket}{\llbracket V \rrbracket^2} :$
Channel length modulation parameter	$\lambda_{Ln} := 0.1 \cdot \frac{\llbracket um \rrbracket}{\llbracket V \rrbracket} :$	$\lambda_{Lp} := 0.1 \cdot \frac{\llbracket um \rrbracket}{\llbracket V \rrbracket} :$
Gate oxide capacitance per unit area	$C_{ox} := 2.3 \frac{\llbracket fF \rrbracket}{\llbracket um \rrbracket^2} :$	
Overlap capacitance	$C_{ov} := 0.5 \frac{ \llbracket fF \rrbracket}{ \llbracket um \rrbracket} :$	
Zero-bias planar bulk depletion capacitance	$C_{Jn} := 0.1 \frac{\llbracket fF \rrbracket}{\llbracket um \rrbracket^2} :$	$C_{Jp} := 0.3 \frac{\llbracket fF \rrbracket}{\llbracket um \rrbracket^2} :$
Zero-bias sidewall bulk depletion capacitance	$C_{JSWn} := 0.5 \frac{\llbracket fF \rrbracket}{\llbracket um \rrbracket} :$	$C_{JSWp} := 0.35 \frac{\llbracket fF \rrbracket}{\llbracket um \rrbracket} :$
Zero-bias well-to-substrate capacitance	-	$C_{Jwell} := 0.05 \frac{ [fF]}{ [um]^2} :$
Bulk junction potential	PB:=0.95[[V]]:	
Planar bulk junction gradient coefficient	MJ := 0.5:	
Sidewall bulk junction gradient coefficient	$MJSW := \frac{1}{3}$:	
Length of source and drain diffusions	$L_{diff} := 3 \llbracket um \rrbracket :$	
Backgate effect parameter	$ \gamma_n := 0.6 \llbracket V \rrbracket^{\frac{1}{2}} : $	$\gamma_p := 0.6 \llbracket V \rrbracket^{\frac{1}{2}}$:
Surface potential parameter	$\phi_f \coloneqq 0.4 \llbracket V \rrbracket$:	